AMENDMENTS TO THE CLAIMS

1. (Original) A polishing composition for a substrate for memory hard disk, comprising silica particles in an aqueous medium, wherein the silica particles satisfy a relationship between an average particle size (r) of the silica particles on the number basis and a standard deviation (σ) on the number basis of the following formula (1):

$$\sigma \ge 0.3 \times r (1)$$

wherein r is an average particle size (nm) of the silica particles on the number basis, and σ is a standard deviation (nm) on the number basis, wherein the average particle size is obtained by a determination by transmission electron microscope (TEM) observation, and wherein a relationship between a particle size (R) and a cumulative volume frequency (V) in a range of particle sizes of from 60 to 120 nm satisfies the following formulas (2) and (3):

$$V \ge 0.5 \times R (2)$$

$$V \le 0.25 \times R + 75 (3)$$

wherein R is a particle size (nm) of the silica particles, and V is a cumulative volume frequency (%) counted from a small particle size side of the silica particles.

2. (Original) The polishing composition according to claim 1, wherein the silica particles are colloidal silica particles.

- 3. (Original) The polishing composition according to claim 1, further comprising at least one member selected from the group consisting of acids, salts thereof and oxidizing agents.
- 4. (Original) The polishing composition according to claim 2, further comprising at least one member selected from the group consisting of acids, salts thereof and oxidizing agents.
- 5. (Original) The polishing composition according to claim 1, wherein a pH thereof is from 1 to 4.5.
- 6. (Original) The polishing composition according to claim 2, wherein a pH thereof is from 1 to 4.5.
- 7. (Original) The polishing composition according to claim 3, wherein a pH thereof is from 1 to 4.5.
- 8. (Original) The polishing composition according to claim 4, wherein a pH thereof is from 1 to 4.5.
- 9. (Original) A method of reducing microwaviness of a substrate for memory hard disk, comprising the step of polishing

the substrate for memory hard disk with the polishing composition of claim 1.

- 10. (Original) A method of reducing microwaviness of a substrate for memory hard disk, comprising the step of polishing the substrate for memory hard disk with the polishing composition of claim 2.
- 11. (Original) A method of reducing microwaviness of a substrate for memory hard disk, comprising the step of polishing the substrate for memory hard disk with the polishing composition of claim 3.
- 12. (Original) A method of reducing microwaviness of a substrate for memory hard disk, comprising the step of polishing the substrate for memory hard disk with the polishing composition of claim 4.
- 13. (Original) A method of reducing microwaviness of a substrate for memory hard disk, comprising the step of polishing the substrate for memory hard disk with the polishing composition of claim 5.
- 14. (Original) A method of reducing microwaviness of a substrate for memory hard disk, comprising the step of polishing

the substrate for memory hard disk with the polishing composition of claim 6.

- 15. (Currently Amended) A method for manufacturing a substrate for memory hard disk, comprising the step of polishing [[an]] a Ni-P plated substrate for memory hard disk with the polishing composition of claim 1.
- 16. (Currently Amended) A method for manufacturing a substrate for memory hard disk, comprising the step of polishing [[an]] a Ni-P plated substrate for memory hard disk with the polishing composition of claim 2.
- 17. (Currently Amended) A method for manufacturing a substrate for memory hard disk, comprising the step of polishing [[an]] \underline{a} Ni-P plated substrate for memory hard disk with the polishing composition of claim 3.
- 18. (Currently Amended) A method for manufacturing a substrate for memory hard disk, comprising the step of polishing [[an]] a Ni-P plated substrate for memory hard disk with the polishing composition of claim 4.

19. (Currently Amended) A method for manufacturing a substrate for memory hard disk, comprising the step of polishing [[an]] a Ni-P plated substrate for memory hard disk with the polishing composition of claim 5.

20. (Currently Amended) A method for manufacturing a substrate for memory hard disk, comprising the step of polishing [[an]] a Ni-P plated substrate for memory hard disk with the polishing composition of claim 6.